

Fig. 1

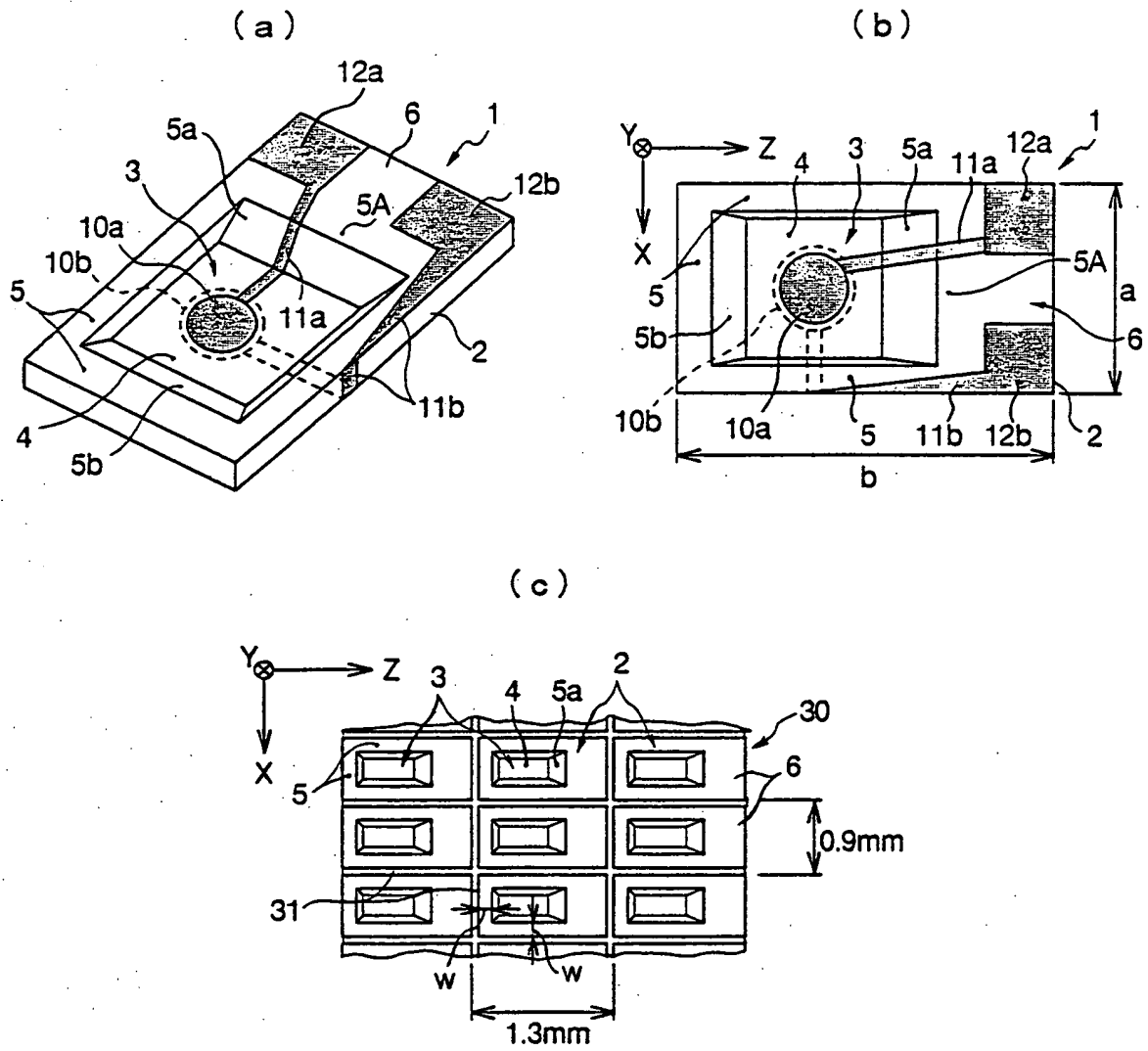


Fig. 2

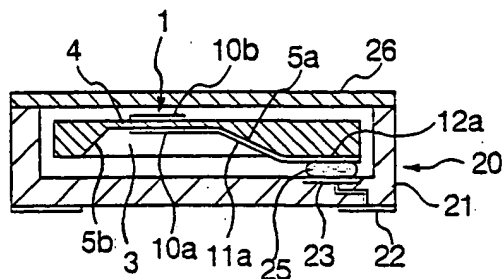


Fig. 3

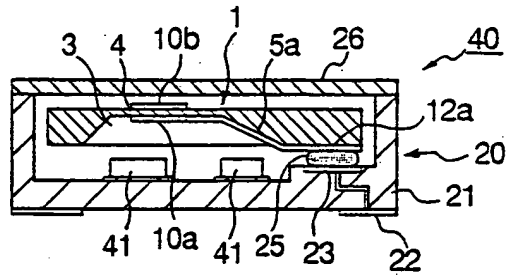


Fig. 4

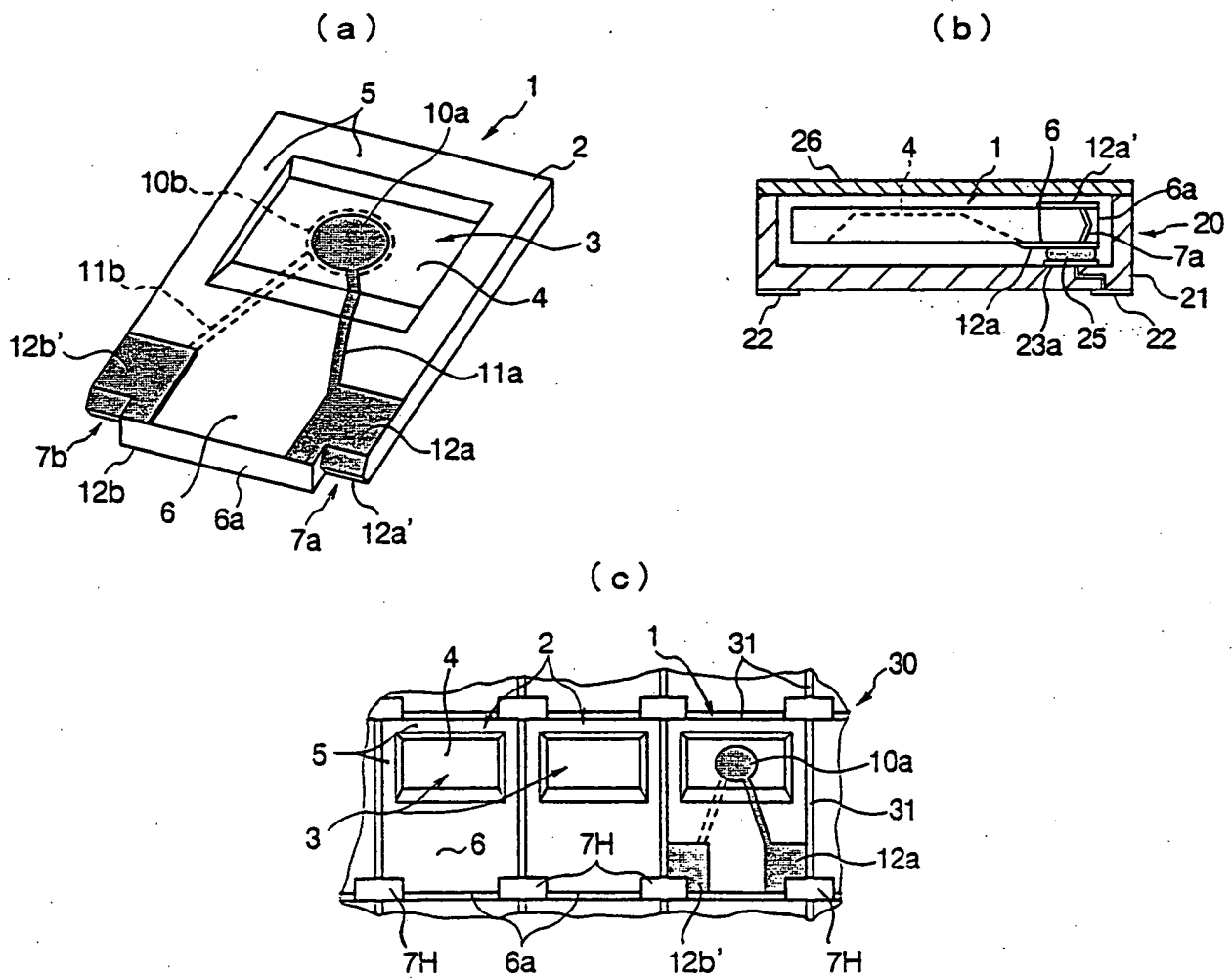


Fig. 5

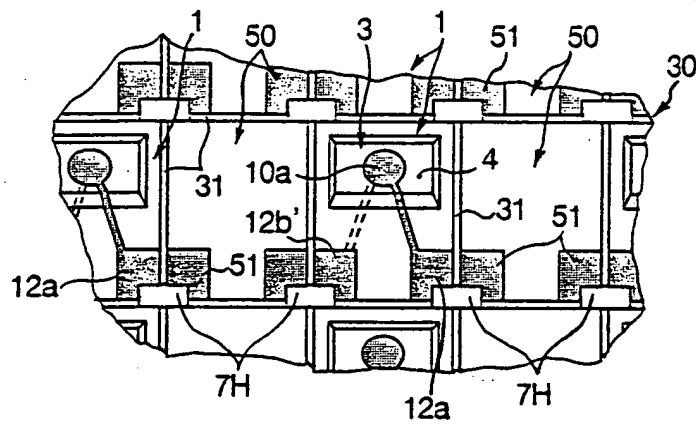
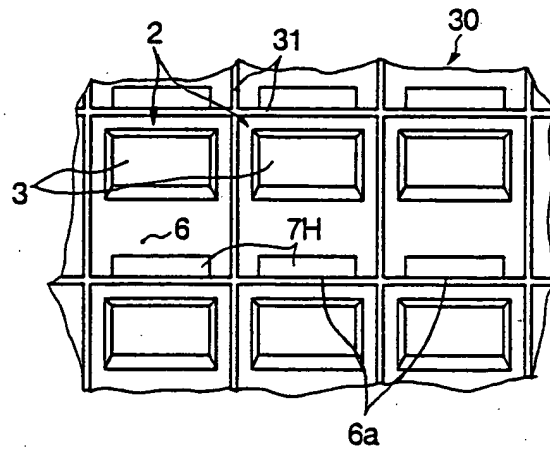


Fig. 6

(a)



(b)

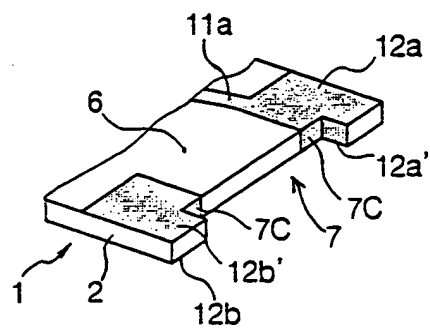


Fig. 7

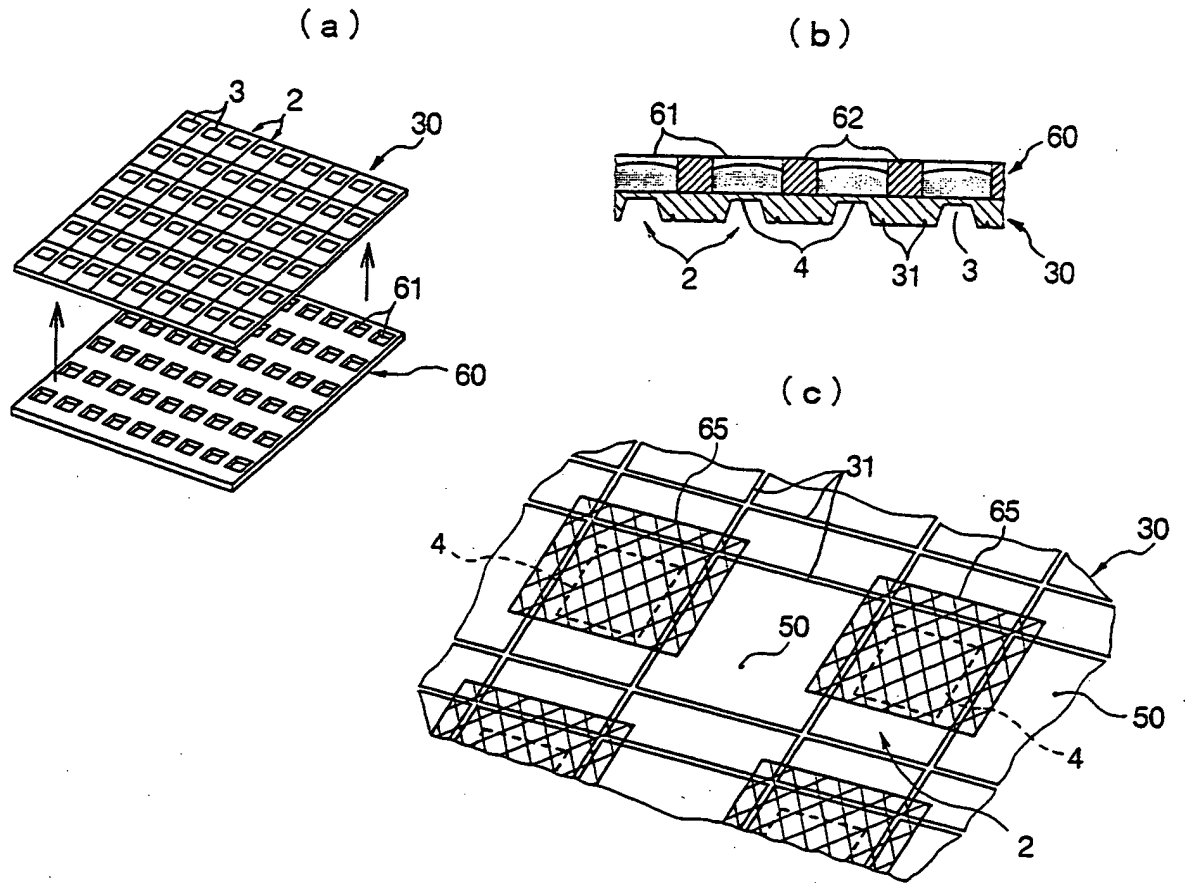


Fig. 8

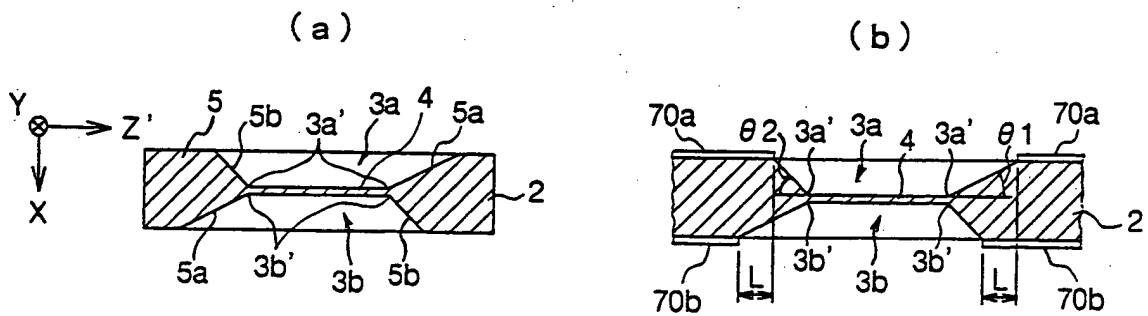
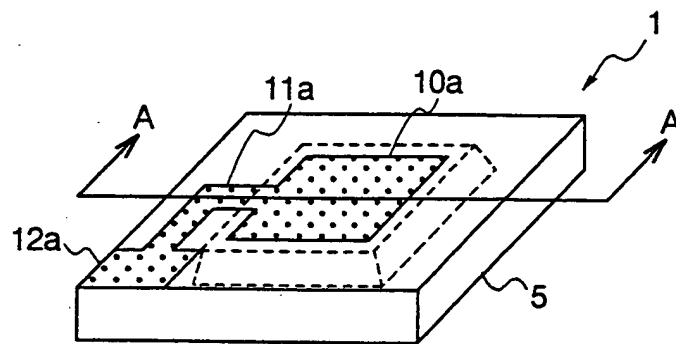


Fig. 9

(a)



(b)

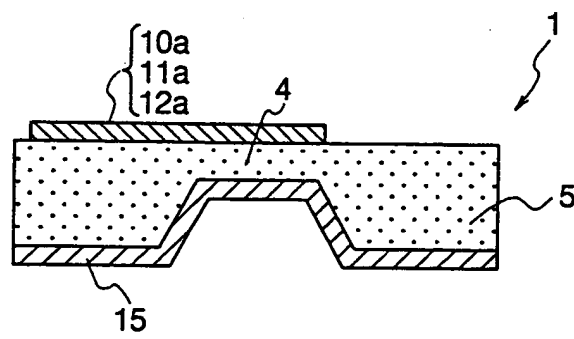


Fig. 10

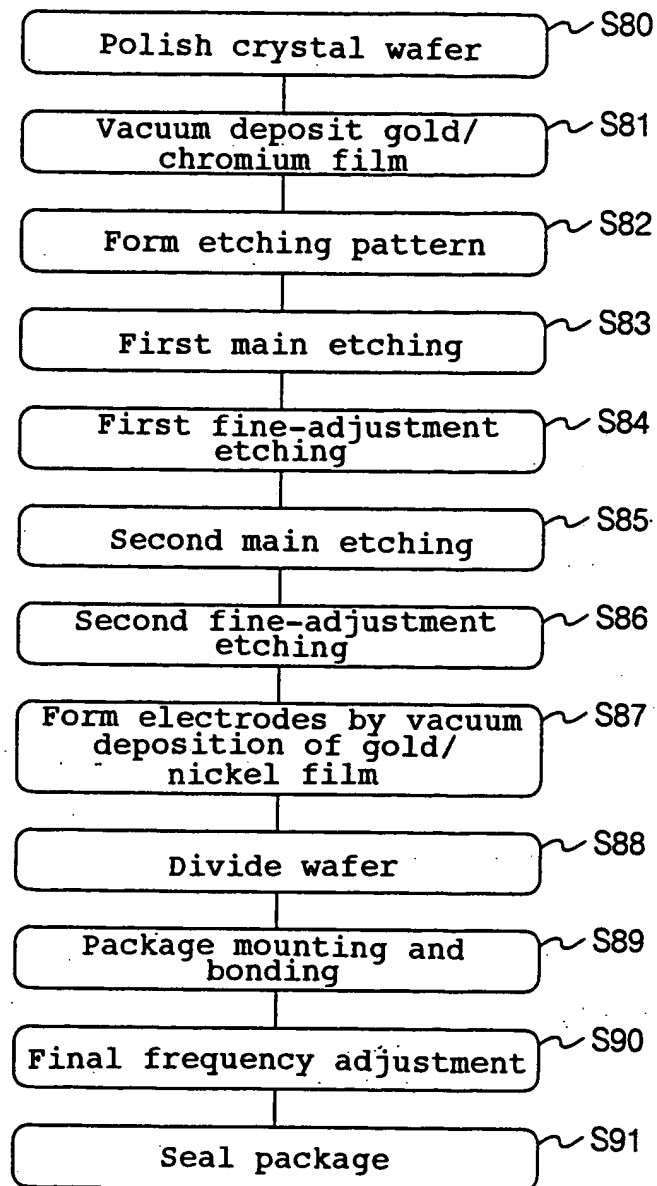
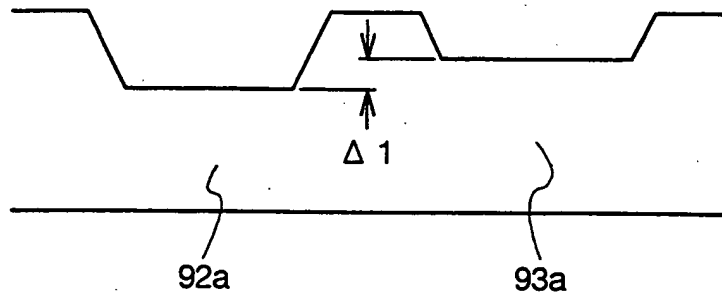


Fig. 11

(a)



(b)

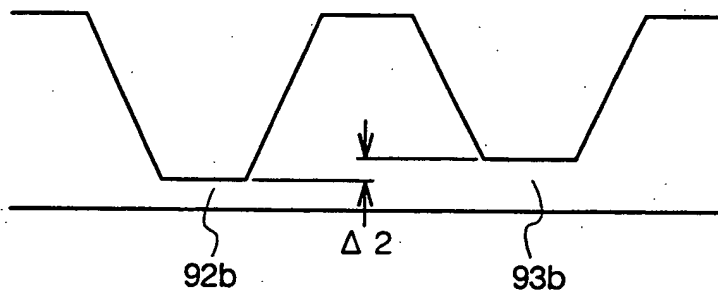


Fig. 12

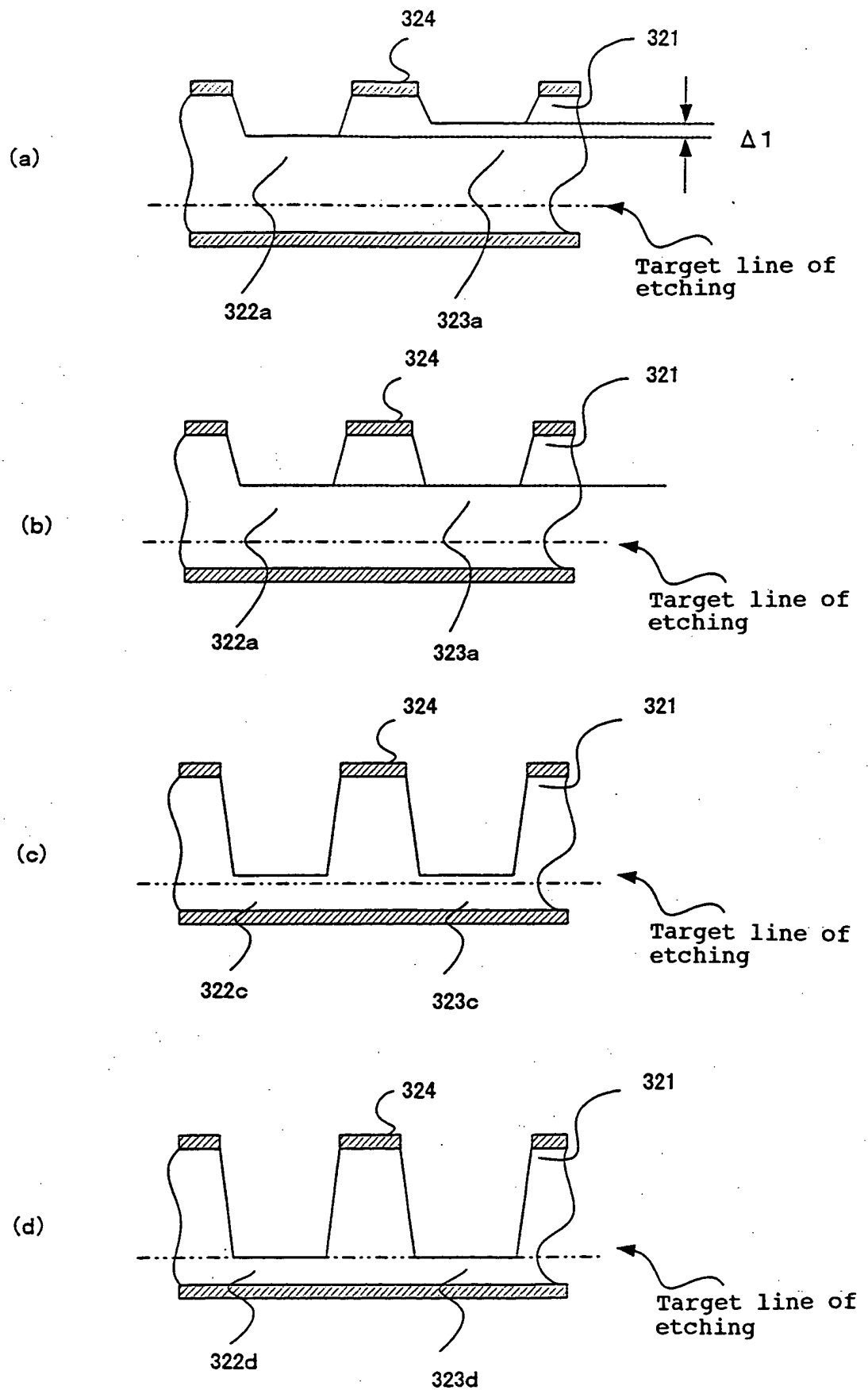


Fig. 13

	Etching conditions		Etching rate [nm/sec]	Adjustment accuracy [nm/sec]
First main etching	Etchant	NH ₄ HF ₂	25	±612
	Temperature	85°C		
First fine-adjustment etching	Etchant	23% Dilute HF	1.5	±93
	Temperature	21°C		
	Etchant	12% Dilute HF	0.75	
	Temperature	21°C		
Second main etching	Etchant	NH ₄ HF ₂	25	±110
	Temperature	85°C		
Second fine-adjustment etching	Etchant	23% Dilute HF	1.5	
	Temperature	21°C		
	Etchant	12% Dilute HF	0.75	
	Temperature	21°C		

Fig. 14

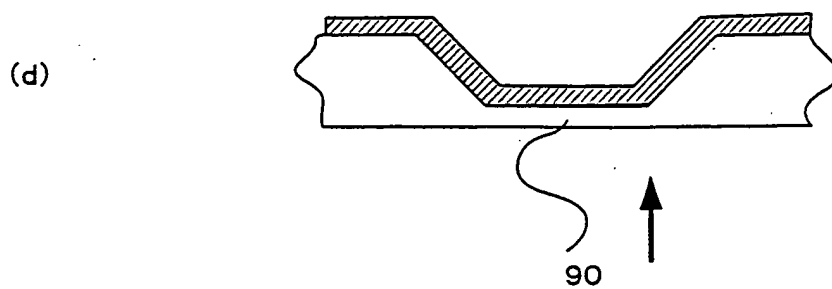
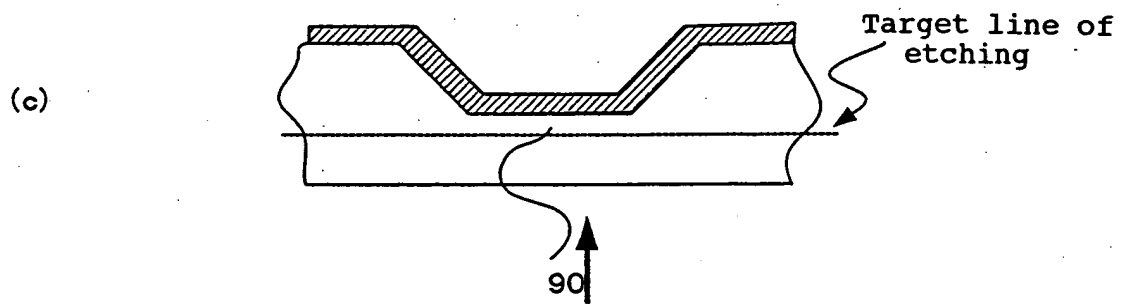
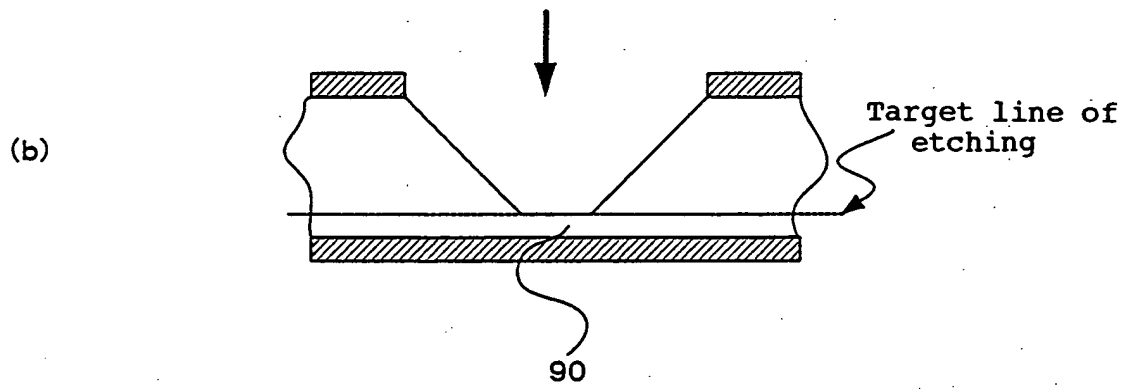
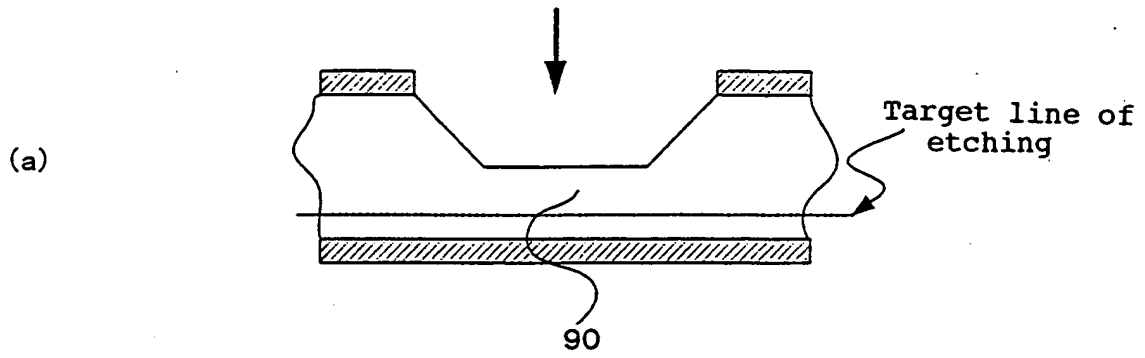


Fig. 15

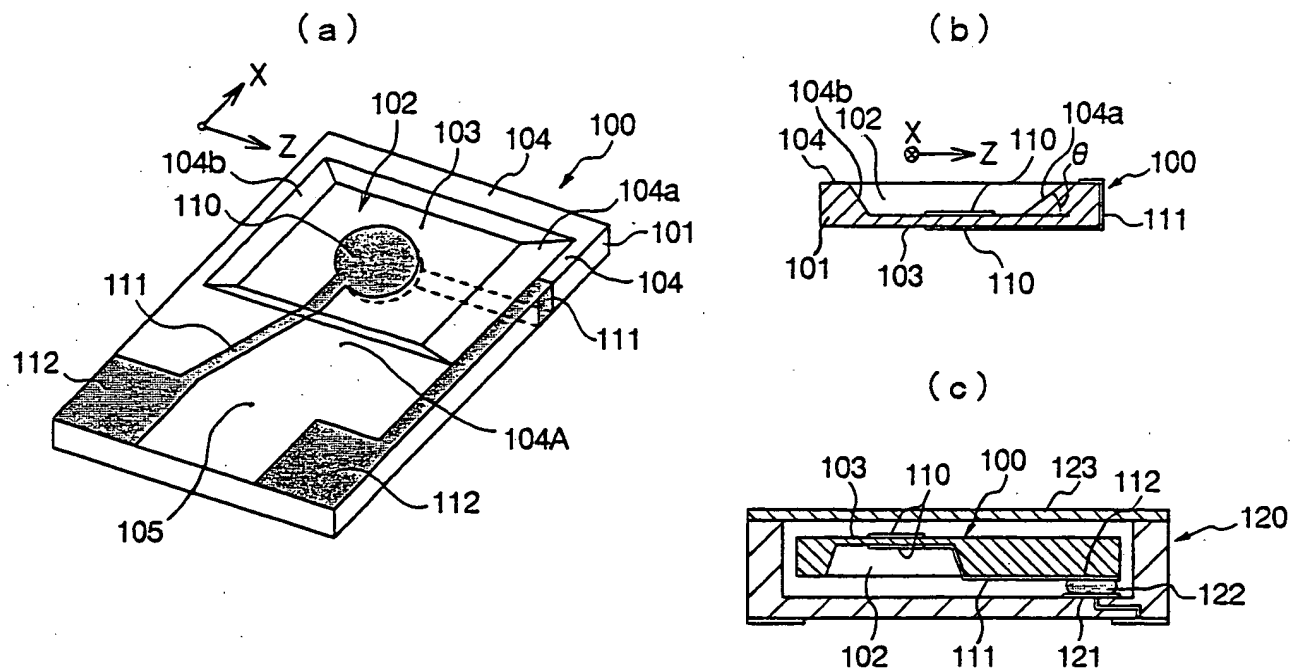


Fig. 16

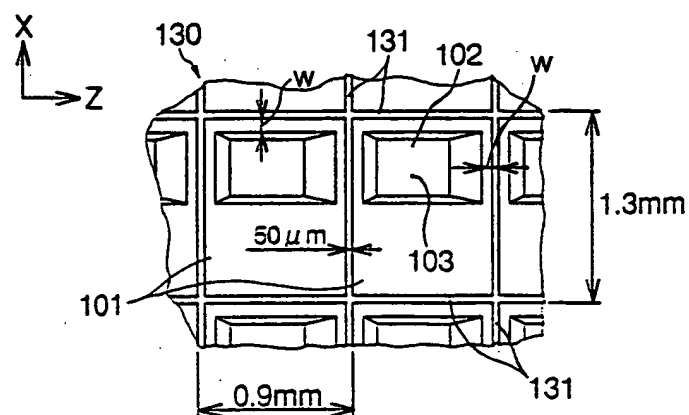


Fig. 17

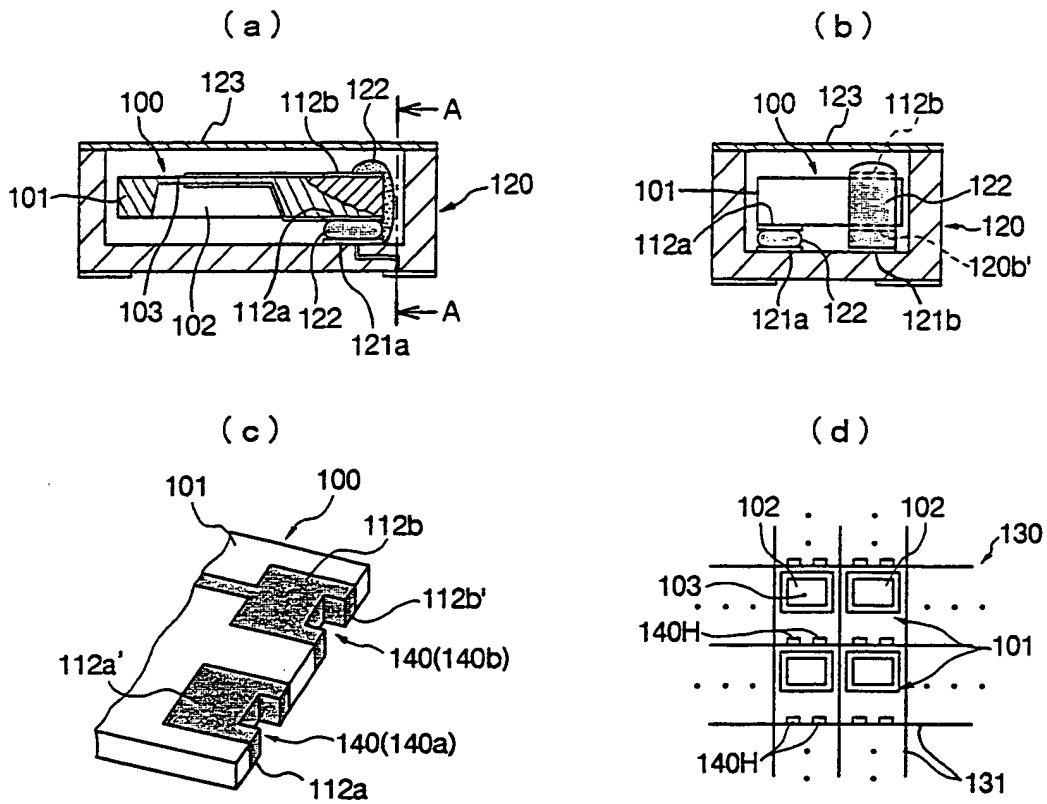


Fig. 18

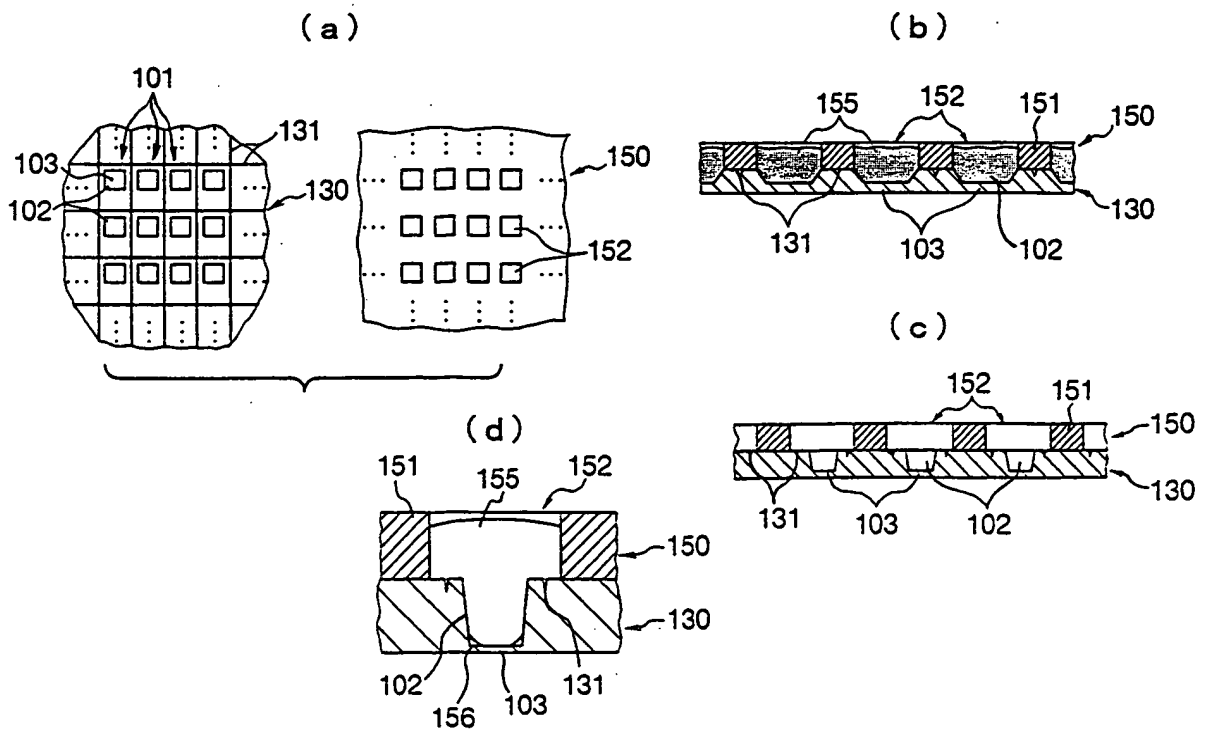


Fig. 19

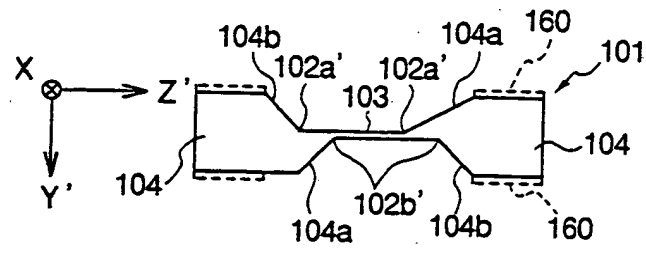


Fig. 20

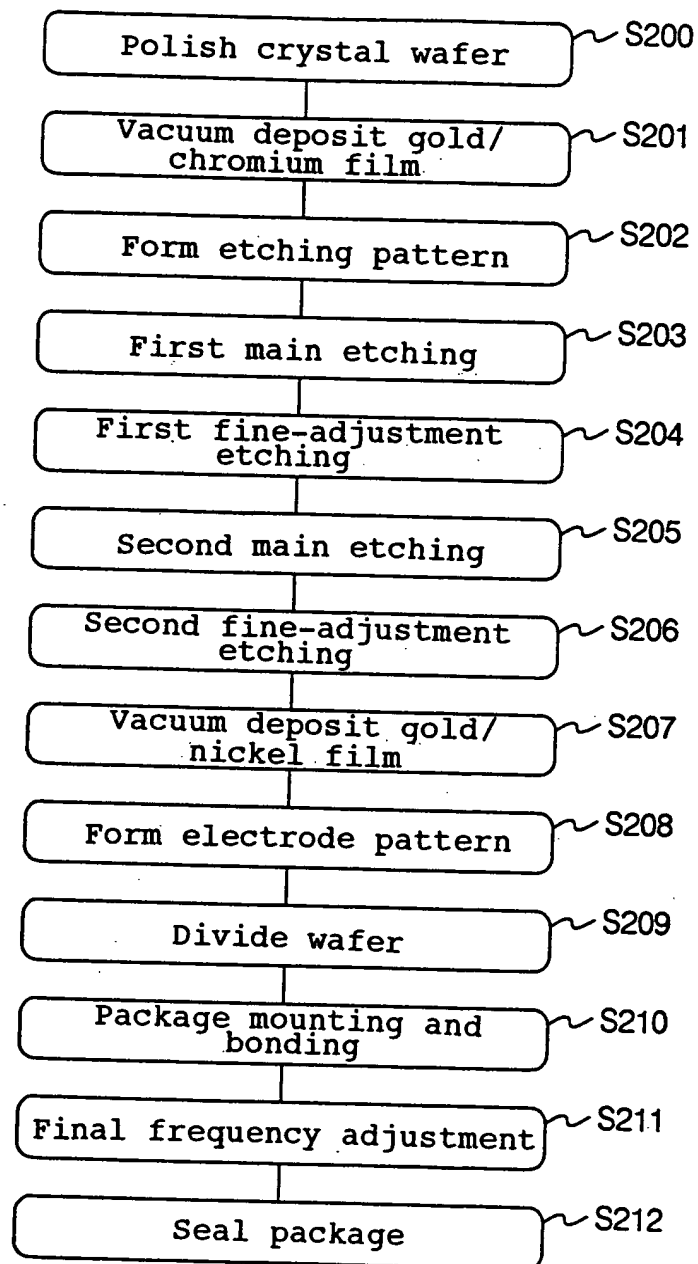
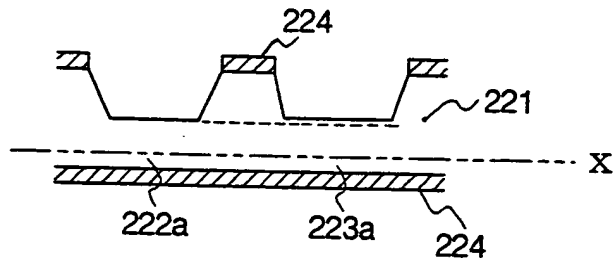
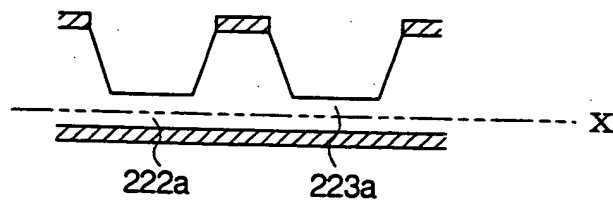


Fig. 21

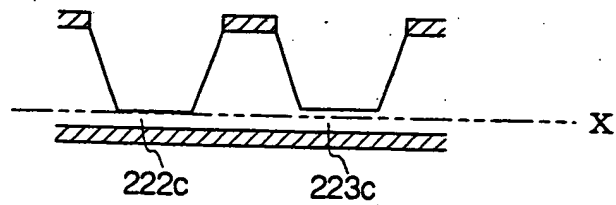
(a)



(b)



(c)



(d)

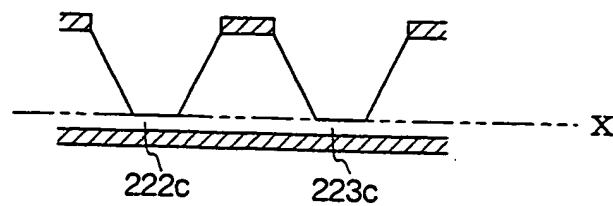


Fig. 22.

